

REMARKS

Applicant responds herein to the Office Action dated March 18, 2004.

Responsive to the Office Action, applicant respectfully disagrees with the assertion in the Patent Office that the claims are not directed to an atomic layer deposition apparatus. In fact, the preamble is of the type that imbues the claim with life and vitality. More importantly, within the body of the claim, it is recited that a gas supply and the controllers which operate it, form an ultra-thin film on the substrate.

Regardless, in order to streamline the prosecution of the application, the applicant has amended the main independent claim by adding the feature that after the first gas is supplied into the reactive chamber, a vacuum pumps evacuates the space in the reactive chamber in order not to mix the first gas and the second gas with one another. Alternatively, supplying a first gas and a second gas and vacuuming the chamber between supplying the first and second gases enables atomic layer deposition on a substrate without a purge process. The foregoing aspect of claim is not disclosed in any of the cited references.

Accordingly, the Examiner is respectfully requested to reconsider the application, allow the claims as amended and pass this case to issue.

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Mail Stop AF, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on June 16, 2004

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Name of applicant, assignee or
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Signature

June 16, 2004

Date of Signature

Respectfully submitted,

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